

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2361	438/243.ccls. 438/248.ccls. 438/268.ccls. 438/296.ccls. 438/391.ccls.	US-PGPUB; USPAT	OR	OFF	2005/11/12 18:08
L2	193	438/248.ccls.	US-PGPUB; USPAT	OR	OFF	2005/11/12 18:20
L3	333	((trench groov\$6) with (polysilicon "poly-si" polycrystalline silicon si)) same (isolation sti) same nitride same (planari\$8 near2 (coating layer film sog glass material))	US-PGPUB; USPAT	OR	ON	2005/11/12 20:04
L5	31	3 same (storage node capacitor deep)	US-PGPUB; USPAT	OR	ON	2005/11/12 18:56
L6	3	2 and 3	US-PGPUB; USPAT	OR	ON	2005/11/12 20:05
L7	4164	((trench groov\$6) with (polysilicon "poly-si" polycrystalline silicon si)) and (isolation sti) and nitride and (planari\$8 near2 (coating layer film sog glass material))	US-PGPUB; USPAT	OR	ON	2005/11/12 18:17
L8	140	((trench groov\$6) with (polysilicon "poly-si" polycrystalline silicon si)) and (isolation sti) and nitride and (planari\$8 near2 (coating layer film sog glass material))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/12 19:48
L9	35	2 and 7	US-PGPUB; USPAT	OR	ON	2005/11/12 19:44
L10	11	8 and (storage node capacitor deep)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/12 19:45
L11	1	"20050070108".pn.	US-PGPUB; USPAT	OR	OFF	2005/11/12 19:44
L12	234	((((trench groov\$6) with (polysilicon "poly-si" polycrystalline silicon si)) with (isolation sti)) same nitride same (planari\$8 near2 (coating layer film sog glass material))	US-PGPUB; USPAT	OR	ON	2005/11/12 20:05
S1	1	"20020196651".pn.	US-PGPUB; USPAT	OR	OFF	2005/11/12 18:06